

	Hits	Search Text	DBs
41	20	((resist or photoresist) same (wafer or workpiece or substrate)) and ((first or initial) same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((second near16 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near5 writ\$4) or maskless)) and pitch\$4 and linewidth and ((imprint\$4 or ion\$3beam or e\$2beam or (electron near4 beam)) near5 (system or apparatus or module)) and (second near29 (photoresist or resist) near29 (expos\$4 or mask or photomask))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
42	0	((resist or photoresist) same (wafer or workpiece or substrate)) and ((first or initial) same (expos\$4 or illuminat\$4 or irradiat\$4)) and (((second near16 (expos\$4 or irradiat\$4 or illuminat\$4)) near36 (mask or photomask or reticle or optical or (direct near5 writ\$4) or maskless)) same (break or bridge or continuity or noncontiguous) same (array or line\$6space or grat\$4)) and pitch\$4 and linewidth	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
43	17	((resist or photoresist) same (wafer or workpiece or substrate)) and ((first or initial) same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((second near16 (expos\$4 or irradiat\$4 or illuminat\$4) near36 (mask or photomask or reticle or optical or (direct near5 writ\$4) or maskless)) same (break or bridge or continuity or noncontiguous) same (array or line\$6space or grat\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB